Bipolar Pulsed Sputtering Power Supply

Product Code: Bipolar pulsed sputtering power supply
Weight: 50.00kg
Dimensions: 145.00cm x 125.00cm x 85.00cm

Short Description

This unit is suitable for metal, alloy, graphite, silicon-aluminum and other targets to coat metal film, carbon film and partial oxide, nitride, carbide film.

Description

Features:

1: Its main loop topology adopts PFC+full bridge architecture combined with ARM+DSP digital control technology

2: It has a built-in arc extinguishing time setting of 10?s-100?s to adapt to different processes and targets. Arc display counts

3: Its output frequency 10-120KHZ pulse interval 1-10?s

4: Constant power, constant current, constant voltage to meet any process requirements

5: It can significantly improve the charge accumulation phenomenon on the target surface, reduce the number of firings on the sputtering surface, and improve the quality of the film.

6: Pulse & DC output in two modes to meet different process requirements.

7: The operation can be controlled by the panel. The remote PLC controls the analog PROFIBUS communication.

Specification

Techanical parameters	
Communication Interface	16GB
Input Voltage & Frequency	IPS
Output current	48"
Output Power	2560 x 1600
Output voltage	Intel HD Graphics
Work mode	Windows 7
Working frequency	Intel Core i5